onsemí

| E ST | UQFN10 1.4x1.8, 0.4F CASE 523BC ISSUE B | 5 | | | |
|---|--|---|---|---|--|
| | | | | DA | TE 13 MAY 2022 |
| ○ 0.05 C | NDTI | ES | | | |
| PIN 1 REFERENCE | 3. | ALL MILLIMET DIMENSIE TERMINA BETWEEN | E Y14.5, DIMENSIO ERS JN b AP S AND N 0.15mm MINAL TII RITY AI PAD A _S | 2018 INS A PLIES TE IS AND 0.30 P, PPLIES S WELL | |
| (A3) | | DIM | | LLIMETE | |
| | - | | MIN. | | MAX. |
| | r | A | 0.45 | 0.50 | 0.55 |
| PLANE SIDE VIEW | - | A1 | 0.00 | 0.025 | 0.05 |
| | - | A3 | | 152 REF | |
| | - | b D | 0.15 | 0.20 | 0.25 |
| ^{9× L} 3 1 | - | E | 1.35 | 1,40 | 1.45 |
| | - | e | 1.75 | 1.80 0.40 BS(| 1.85 |
| | - | е I | 0.35 | 0.40 830 | 0.45 |
| $\begin{array}{c} \text{PIN I} \\ \text{REFERENCE} \\ 1.25L \\ \text{BETTEM VIEW} \end{array} $ | 0.663 0.663 0.4000 10X 0.225 RECOM LAND P/ RECCI For addit Pb-Free please do and Moun Manual, S | MENDED MENDED tional inf strategy pwnload t iting Teck | 563 0.5 0 0, 10X | FOUTPRIN on our dering den i Solderi | SOU - 9X 0.4500 1.8500 - 1.8500 - 1.8500 - AL MINIMIAL ND PATTERN NT etails, ng |

| DOCUMENT NUMBER: | 98AON13705G | Electronic versions are uncontrolled except when accessed directly from the Document Repository. Printed versions are uncontrolled except when stamped "CONTROLLED COPY" in red. | | | | |
|--|----------------------|---|-------------|--|--|--|
| DESCRIPTION: | UQFN10 1.4x1.8, 0.4P | | PAGE 1 OF 1 | | | |
| onsemi and ONSEMI are trademarks of Semiconductor Components Industries, LLC dba onsemi or its subsidiaries in the United States and/or other countries. onsemi reserves | | | | | | |

the right to make changes without further notice to any products herein. onsemi makes no warranty, representation or guarantee regarding the suitability of its products for any particular purpose, nor does onsemi assume any liability arising out of the application or use of any product or circuit, and specifically disclaims any and all liability, including without limitation special, consequential or incidental damages. onsemi does not convey any license under its patent rights of others.